

Form PTO-1449
(Rev. 8-83)U.S. Department of Commerce
Patent and Trademark Office

Atty. Docket No.: 0756-1894

Serial No. 09/197,534

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Applicant: Shunpei YAMAZAKI et al.

Filing Date: 11/23/98

Group: 1762

U.S. PATENT DOCUMENTS

Examiner Initial	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)
	4,370,175	01/25/83	Levatter			
	5,306,651	04/26/94	Masumo et al.			

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	60-245125	12/04/85	Japan			X	
	61-80815	04/24/86	Japan			X	
	60-257511	12/19/85	Japan			X	
	4-338631	11/25/92	Japan			X	
	63-25933	02/03/88	Japan			X	
	1-241862	09/26/89	Japan			X	
	5-21339	01/29/93	Japan			X	
	60-227484	11/12/85	Japan			X	
	61-141174	06/28/86	Japan			X	
	55-32026	03/06/80	Japan			X	

OTHER DOCUMENTS (Including Author, Title, Relevant Pages, Date, Place of Publication)

	"Applications of Excimer Lasers in Microelectronics", Tim McGrath, Lasertechnics, Inc., Albuquerque, New Mexico, Solid State Technology/December 1983, pp. 165-169
	"High-Performance TFT's Fabricated by XeCl Excimer Laser Annealing of Hydrogenated Amorphous-Silicon Film, Kenju Sera et al., IEEE Transactions on Electron Devices, Vol. 36, No. 12, December 1989, pp. 2868-2872.
	Semiconductor World, Chapter 2, Active Element Array Forming Technology Annealing Apparatus, Excimer Laser Annealing Apparatus Leonix, pp. 196-197
	Special Article: Present Situation of Laser Processing Technique, Application of Surface Modification by CO ₂ Laser, Akira Morikawa et al., Laser Group, Engineering Section, Mechatronics Apparatus Division, pp. 68-69
	"Excimer Laser Annealed Poly-Crystalline Silicon TFT, Setsuo Kaneko, T. IEEE Japan, Vol. 110-A, No. 10, 1990, pp. 679-683
	Semiconductor World, Chapter 2, Active Element Array Forming Technology Annealing Apparatus, Excimer Laser Annealing Apparatus Leonix, 1993, pp.196-197
	"XeCl Excimer Laser Annealing Used to Fabricate Poly-Si TFT's", Toshiyuki Sameshima et al., Japanese Journal of Applied Physics, Vol. 28, No. 10, October 1989, pp. 1789-1793

Examiner

Date Considered September 26, 2001

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.